



Attorney Docket No. 99154X204201

PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of:

Fang et al.

Application No. 09/595,227

Filed: June 16, 2000

For: METHOD FOR POLISHING A
MEMORY OR RIGID DISK WITH A
PHOSPHATE ION-CONTAINING
POLISHING SYSTEM

Art Unit: 3723

Examiner: H. Shakeri

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JAN 23 2002
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RESPONSE TO OFFICE ACTION

Commissioner for Patents
Washington, D.C. 20231

01/25/2002 NCHAPMAN 00000003 121216 09595227
Dear Sir:
01 FC:215 55.00 CH

In response to the Office Action dated September 25, 2001, please enter the following amendments and consider the following remarks.

AMENDMENTS

IN THE SPECIFICATION:

Replace the paragraph appearing at page 2, lines 17-27, with the following paragraph:

The present invention provides a method of planarizing or polishing the surface of a memory or rigid disk, as well as a polishing system useful in such a method. The method comprises contacting the surface of a memory or rigid disk with a polishing system comprising (i) a polishing composition comprising water, an oxidizing agent, and about 0.04 M or higher phosphate ion or phosphonate ion, and (ii) abrasive material, and abrading at least a portion of the surface of the memory or rigid disk by movement of the polishing system relative to the surface of the memory or rigid disk. Such contacting and abrading can take place by any suitable technique. For example, the polishing system can be applied to the surface of the memory or rigid disk and used to abrade at least a portion of the surface of the memory or rigid disk through use of a polishing pad.

01/17/2002 JADD01 00000053 09595227

01 FC:203

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